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AUG 18 2004  
PATENT & TRADEMARK OFFICE  
0321.67421

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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In U.S. Patent Application of: )  
Applicant(s): Andrew B. Kahng )  
Serial No.: 10/787,070 )  
Conf. No.: 2850 )  
Filed: February 25, 2004 )  
For: METHOD FOR CORRECTING A )  
MASK DESIGN LAYOUT )  
Art Unit: 2825 )  
Examiner: Unassigned )

I hereby certify that this paper is being deposited with the United States Postal Service as FIRST-CLASS mail in an envelope addressed to: Mail Stop Amendment, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on this date.

August 16, 2004  
Date

  
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INFORMATION DISCLOSURE STATEMENT

Mail Stop Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

This IDS is submitted under 37 C.F.R. §1.97(b) within either of the following time periods, whichever occurs last:

- (a) within three months of either the filing date of the national application or the date of entry into the national stage; or
- (b) before the mailing date of first office action on the merits (i.e., not including actions such as restriction requirements).

Applicant(s) submit herewith Form PTO-1449 (Information Disclosure Citation) together with copies of patents, publications or other information of which applicant(s) are aware, which applicant(s) believe may be material to the examination of this application and for which there may be a duty to disclose in accordance with 37 C.F.R. §1.56. Applicant(s) respectfully submit that the citation of any reference on Form PTO-1449 does not constitute an admission that the reference qualifies as prior art.

It is requested that the information disclosed on the enclosed Form PTO-1449 be made of record in this application.

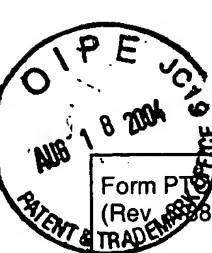
The Commissioner is hereby authorized to charge any additional fees which may be required to this application under 37 C.F.R. §§1.16-1.17, or to credit any overpayment, to Deposit Account No. 07-2069. A duplicate copy of this sheet is enclosed.

Respectfully submitted,

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Form PTO-1449 (Rev. 08/98) <b>INFORMATION DISCLOSURE CITATION</b> (Use several sheets if necessary)	Attorney Docket No.: 0321.67421	Serial No.: 10/787,070
	Applicant: Andrew B. Kahng et al.	
	Filing Date: February 25, 2004	Group: 2825

**U.S. PATENT DOCUMENTS**

Examiner Initial*	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate

**FOREIGN PATENT DOCUMENTS**

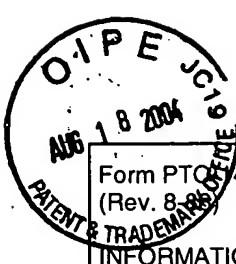
	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No

**OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)**

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Examiner	Date Considered
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\*Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.



<p>Form PTO-1449 U.S. Department of Commerce            (Rev. 8-8-95) U.S. Patent and Trademark Office</p> <p><i>TRADEMARKS</i></p> <p>INFORMATION DISCLOSURE CITATION            (Use several sheets if necessary)</p>	<p>Attorney Docket No.: 0321.67421</p>	<p>Serial No.: 10/787,070</p>
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## U.S. PATENT DOCUMENTS

## **FOREIGN PATENT DOCUMENTS**

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